

## Problem:

- GaSb/InAs heterojunction TFETs are NOT scalable  $\leftarrow$  large tunneling leakage  $\leftarrow$  small band gap and effective mass of the InAs channel

## Objective:

- To have a scalable design

## Approach:

Non-uniform body thickness design:

- Thin InAs channel  $\rightarrow$  a large band gap and large effective masses  $\rightarrow$  small tunnel leakage at OFF state
- Thick GaSb/InAs tunnel junction  $\rightarrow$  a low tunnel barrier and small tunnel effective masses  $\rightarrow$  large tunnel probability at ON state

## Results / Impact:

- @  $L_g = 15\text{nm}$ ,  $V_{DD} = 0.3\text{V}$  and  $I_{OFF} = 1\text{nA}/\mu\text{m}$ ,  $I_{ON} = 284\mu\text{A}/\mu\text{m}$ , an order of magnitude larger than the uniform case ( $25\mu\text{A}/\mu\text{m}$ ).
- Scalable to sub-10nm channel length

